

L Number	Hits	Search Text	DB	Time stamp
1	3748	silicon same (micro near machin\$3 or "MEMS")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:51
2	14187	(photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:01
3	0	((silicon same (micro near machin\$3 or "MEMS")) same ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 18:51
4	38	((silicon same (micro near machin\$3 or "MEMS")) and ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 18:52
5	3	((silicon same (micro near machin\$3 or "MEMS")) and ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3))) and @pd<20000524	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 18:52
6	298	((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 20:12
7	45	((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and @pd<20000524	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:02
8	17	((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and 216/2.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:25
10	0	((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and 216/2.ccls.) and insulat\$3) and (backside near etch\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:26
9	12	((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and 216/2.ccls.) and insulat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:44
11	1	("5569355").PN.	USPAT; US-PGPUB	2003/07/09 19:46
12	17	(deep near lithograph\$2) same (micro near machin\$3 or "MEMS")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:56
13	0	"5569355".pn. and ("MEMS")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:56
14	561	((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2 or lithograph\$2))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 20:12

15	413	((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2 or lithograph\$2)) and (silicon same etch\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 20:14
16	59	((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2 or lithograph\$2)) and (silicon same etch\$3)) and @pd<20000524	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 20:16

L Number	Hits	Search Text	DB	Time stamp
1	3748	silicon same (micro near machin\$3 or "MEMS")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 18:49
2	14187	(photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:01
3	0	((silicon same (micro near machin\$3 or "MEMS"))) same ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 18:51
4	38	((silicon same (micro near machin\$3 or "MEMS"))) and ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 18:52
5	3	((silicon same (micro near machin\$3 or "MEMS"))) and ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3))) and @pd<20000524	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 18:52
6	298	((silicon same (micro near machin\$3 or "MEMS"))) same (photo near resist or photolithograph\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:24
7	45	((silicon same (micro near machin\$3 or "MEMS"))) same (photo near resist or photolithograph\$2)) and @pd<20000524	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:02
8	17	((silicon same (micro near machin\$3 or "MEMS"))) same (photo near resist or photolithograph\$2)) and 216/2.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:25
10	0	((silicon same (micro near machin\$3 or "MEMS"))) same (photo near resist or photolithograph\$2)) and 216/2.ccls.) and insulat\$3) and (backside near etch\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:26
9	12	((silicon same (micro near machin\$3 or "MEMS"))) same (photo near resist or photolithograph\$2)) and 216/2.ccls.) and insulat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/09 19:26